

IN THE CLAIMS

1-10. (Cancelled)

11. (Currently Amended) A system for aligning a semiconductor wafer and a mask, comprising:

an illumination tool for irradiating the mask so as to create a bright spot thereon by a $[[0_ \pi]]$ 0 to π phase conflict during an illumination;

a detection tool for detecting the bright spot and $[[the]]$ an alignment mark on the semiconductor wafer; and

alignment means for aligning the alignment mark with the bright spot so as to align the semiconductor wafer with the mask.

12. (Original) The system according to claim 11, wherein the alignment mark on the semiconductor wafer is in a form of a frame.

13. (Original) The system according to claim 12, wherein the frame is created to minimize an impact of film stack variations.

14. (Original) The system according to claim 11, wherein the alignment mark on the semiconductor wafer is in a form of a box structure.

15. (Original) The system according to claim 14, wherein the box structure is created to minimize an impact of film stack variations.

16. (Original) The system according to claim 11, wherein the illumination tool generates the alignment mark in a form of a frame.

17. (Original) The system according to claim 16, wherein the illumination tool generates the frame to minimize an impact of film stack variations.

18. (Original) The system according to claim 11, wherein the illumination tool generates the alignment mark in a form of a box structure.

19. (Original) The system according to claim 18, wherein the illumination tool generates the box structure to minimize an impact of film stack variations.

20. (New) A system for aligning a mask and a semiconductor wafer having thereon an alignment mark, comprising:

an illumination tool for irradiating the mask to create a bright spot thereon;

a detection tool for detecting the bright spot and the alignment mark; and

alignment means for aligning the alignment mark with the bright spot so as to align the semiconductor wafer with the mask.

21. (New) The system according to Claim 20, wherein the alignment mark is in a form of a frame.

22. (New) The system according to Claim 21, wherein the alignment means is for framing the bright spot within the alignment mark.